

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of claims:**

What is claimed is:

Claim 1 (original): A positive-acting photoimageable composition comprising a photoactive component and a polymer component,

the polymer component comprising a polymer that comprises Si atoms and silanol groups,

wherein the polymer has a ratio of silanol groups to Si atoms of about 0.01 to 1.5.

Claims 2-4 (cancelled).

Claim 5 (original): The photoimageable composition of claim 1 wherein the ratio of silanol groups to Si atoms is about 0.01 to 0.4.

Claims 6-8 (cancelled).

Claim 9 (currently amended): The photoimageable composition of ~~any one of claims 1 through~~ 8 wherein the polymer comprises aqueous base-solubilizing groups.

Claim 10 (currently amended): The photoimageable composition of claim 9 wherein the aqueous base-solubilizing groups are fluorinated alcohols, sulfonamide, carboxylic acid and/or thiols.

Claim 11 (cancelled).

Claim 12 (currently amended): The photoimageable composition of ~~any one of claims 9 through 11~~ wherein the polymer contains at least about 20 mole percent of aqueous base-solubilizing groups based on total units of the polymer.

Claims 13-14 (cancelled).

Claim 15 (currently amended): The photoimageable composition of ~~any one of claims 9 through 11~~ wherein the polymer contains at least about 50 mole percent of aqueous base-solubilizing groups based on total units of the polymer.

Claim 16 (currently amended): The photoimageable composition of ~~any one of claims 1 through 15~~ wherein the polymer comprises units that are free of photoacid-labile groups and aqueous base-solubilizing groups.

Claim 17 (currently amended): The photoimageable composition of ~~any one of claims 1 through 16~~ wherein the polymer comprises at least two distinct repeat units.

Claims 18-19 (cancelled).

Claim 20 (currently amended): The photoimageable composition of ~~any one of claims 1 through 19~~ wherein the polymer comprises at least three distinct repeat units of: 1) units that contain photoacid-labile groups; 2) units that are free of photoacid-labile and aqueous base-solubilizing groups; and 3) units that comprise an aqueous base-solubilizing group.

Claim 21 (currently amended): The photoimageable composition of ~~any one of claims 1 through 20~~ wherein the composition is a chemically-amplified positive acting photoresist.

Claim 22 (original): The photoimageable composition of claim 1 wherein the composition is a negative-acting photoresist.

Claims 23-29 (cancelled).

Claim 30 (currently amended): A coated substrate comprising:

- a) a polymer composition coating layer applied over a substrate surface;
- b) a coating layer of a photoimageable composition of ~~any one of claims 1 through 29~~ disposed over the polymer composition coating layer.

Claims 31-36 (cancelled):

Claim 37 (currently amended): A coated substrate of ~~any one of claims 30 through 36~~ wherein the polymer composition does not contain a polymer with Si groups.

Claim 38 (currently amended): A coated substrate of ~~any one of claims 30 through 37~~ wherein the polymer composition is not photoimageable.

Claim 39 (currently amended): A method for forming a electronic device, comprising:

- (a) applying on a substrate a coating layer of a polymer composition;
- (b) over the polymer composition coating layer, applying a photoimageable composition of ~~any one of claims 1 through 29~~;
- (c) exposing the photoimageable composition coating layer to activating radiation and developing the exposed photoimageable layer.

Claim 40 (original): The method of claim 39 wherein a coating layer of the photoimageable composition coating layer is exposed with radiation having a wavelength of about 248 nm.

Claim 41 (original): The method of claim 39 wherein a coating layer of the photoimageable composition coating layer is exposed with radiation having a wavelength of less than about 200 nm.

Claim 42 (original): The method of claim 39 wherein a coating layer of the photoimageable composition coating layer is exposed with radiation having a wavelength of about 193 nm or 157 nm.

Claims 43-59 (cancelled).